

Form PTO-1449

Docket No: GB920000043US1

Application No:

INFORMATION DISCLOSURE
CITATION IN AN APPLICATION
(Use several sheets if necessary)

Applicant: Phippen et al

Filing Date:

Group Art Unit:

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Issue Date	Patentee	Class	Subclass	Filing Date If Appropriate
	1A						
	1B						
	1C						
	1D						
	1E						
	1F						

FOREIGN PATENT DOCUMENTS

Examiner Initial		Document Number	Publication Date	Country of Patent Office	Class	Subclass	Translation Yes/No
JB	2A	WO 98/30962	07/16/98	PCT			
	2B						
	2C						
	2D						
	2E						
	2F						
	2G						
	2H						

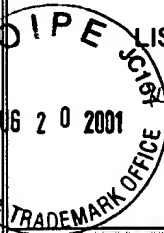
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages etc)

Examiner Initial		
JB	3A	IBM MQSeries Integrator product, versions 1 and 2, http://www-4.ibm.com/software/ts/...ies/library/whitepapers/eai-tech , and http://www-4.ibm.com/software/ts/...pers/mqintegrator/msgbrokers.html
	3B	
	3C	
	3D	

Examiner: JAMES BROWN

Date Considered: 5/21/04

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Form PTO-1449		ATTORNEY DOCKET NO. GB920000043US1		SERIAL NO. 09/764,610	
 LIST OF PRIOR ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT J.M. Knapman, et al			
		FILING DATE		GROUP ART UNIT 2152	
U.S. PATENT DOCUMENTS					
EXAMINER INITIAL	DOCUMENT NO.	PUBLICATION DATE	INVENTOR NAME	CLASS/ SUBCLASS	FILING DATE
FOREIGN PATENT DOCUMENTS					
EXAMINER INITIAL	DOCUMENT NO.	PUBLICATION DATE	COUNTRY	CLASS/ SUBCLASS	TRANSLATION YES NO
JB	A 2304944A	10-24-2000	UK	G06F 9/00	X
OTHER PRIOR ART (including author, title, date, pertinent page, etc.)					
DATE CONSIDERED 5/24/04		EXAMINER JAMES BROWN			
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